

ABSTRACT OF THE DISCLOSURE

A photosensitive composition for sandblasting comprising the components of: (A) a photopolymerizable urethane 5 (meth)acrylate oligomer comprising (meth)acryloyl group; (B) an acrylic copolymer; and (C) a photopolymerization initiator, wherein the component (B) comprises, as a monomer unit, one of copolymerizable monomers comprising one of a benzene ring and a cyclohexyl group.

**BEST AVAILABLE COPY**